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Anti-flare semiconductor packages and related methods

Abstract

Implementations of semiconductor packages may include: a semiconductor die having a first side and a second side. A first side of an optically transmissive lid may be coupled to the second side of the semiconductor die through one or more dams. The packages may also include a light block material around the semiconductor package extending from the first side of the semiconductor die to a second side of the optically transmissive lid. The package may include an opening in the light block material on the second side of the optically transmissive lid that substantially corresponds with an active area of the semiconductor die.

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Background/Summary

CROSS REFERENCE TO RELATED APPLICATIONS (1) This application is a continuation application of the earlier U.S. Utility Patent Application to Shou-Chian Hsu entitled “Anti-Flare Semiconductor Packages and Related Methods,” application Ser. No. 18/363,289, filed Aug. 1,

2023, now pending, which is a divisional application of the earlier U.S. Utility Patent Application to Shou-Chian Hsu entitled “Anti-Flare Semiconductor Packages and Related Methods,” application Ser. No. 17/305,616, filed Jul. 12, 2021, now pending, which application is a continuation application of the earlier U.S. Utility Patent Application to Shou-Chian Hsu entitled “Anti-Flare Semiconductor Packages and Related Methods,” application Ser. No. 16/456,917, filed Jun. 28, 2019, now issued as U.S. Pat. No. 11,063,078, the disclosures of each of which are hereby incorporated entirely herein by reference.

BACKGROUND

1. Technical Field

(1) Aspects of this document relate generally to semiconductor packages, such as complementary metal oxide semiconductor (CMOS) image sensor chip scale packages (CISCSPs) for consumer electronic devices such as cameras, phones, tablets, and laptops. More specific implementations involve image sensor packages having lids.

2. Background

(2) Complementary metal-oxide-semiconductor (CMOS) image sensor chip scale packages (CISCSP) have a broad range of applications due to their small/thin form and low overall cost. Current CISCSPs include a transparent glass covering the entire chip.

SUMMARY

(3) Implementations of semiconductor packages may include: a semiconductor die having a first side and a second side. A first side of an optically transmissive lid may be coupled to the second side of the semiconductor die through one or more dams. The packages may also include a light block material around the semiconductor package extending from the first side of the semiconductor die to a second side of the optically transmissive lid. The package may include an opening in the light block material on the second side of the optically transmissive lid that substantially corresponds with an active area of the semiconductor die.

(4) Implementations of semiconductor packages may include one, all, or any of the following: The second side of the optically transmissive lid may include an indentation on each of a first edge and a second edge of the optically transmissive lid. The light block material may be a molding compound. The semiconductor package may include a redistribution layer coupled to the first side of the semiconductor die. The opening may correspond with a pixel array in the semiconductor die. The semiconductor package may further include one or more die pads coupled to each of the one or more dams. The semiconductor package may further include one or more die pads coupled to each of the one or more dams. The semiconductor package may further include a plurality of through silicon vias (TSVs), a passivation layer, a solder mask, and two or more solder bumps.

(5) Implementations of semiconductor packages may include: a semiconductor die having a first side and a second side and a first side of an optically transmissive lid coupled to the second side of the semiconductor die through one or more dams. A second side of the optically transmissive lid may include a first recess and a second recess on a first edge and a second edge of the optically transmissive lid, respectively. The package may also include a light blocking material encapsulating the semiconductor package from a first side of the semiconductor die into the first recess and into the second recess on the second side of the optically transmissive lid.

(6) Implementations of semiconductor packages may include one, all, or any of the following: The semiconductor package may further include an opening in the light blocking material. The opening may be between the first recess and the second recess on the second side of the optically transmissive lid. The light block material may be a molding compound. The semiconductor package may further include a redistribution layer (RDL) coupled to a first side of the semiconductor die. An active area of the semiconductor die may correspond with the first recess and the second recess in the optically transmissive glass lid. The semiconductor package may further include one or more die pads coupled to each of the one or more dams. The semiconductor

package may further include a plurality of through silicon vias (TSVs), a passivation layer, a solder mask, and two or more solder bumps.

(7) Implementations of semiconductor packages may be formed using implementations of methods for forming semiconductor package, the methods may include: providing an optically transmissive lid having a first side and a second side. The optically transmissive lid may include a plurality of recesses on the second side of the optically transmissive lid. The method may also include coupling a semiconductor wafer to the first side of the optically transmissive lid. The semiconductor wafer may include a first side and a second side. The second side of the wafer may include a plurality of active areas. The method may also include singulating the semiconductor wafer and the optically transmissive lid between each of the plurality of active areas in the wafer to form a plurality of semiconductor packages. The method may include coupling the second side of the optically transmissive lids of each of the semiconductor packages to a carrier wafer. The recesses on the optically transmissive lid may form a space between the carrier wafer and the optically transmissive lids. The method may include applying light blocking material to each of the semiconductor packages. The light blocking material may encapsulate each of the semiconductor packages from a first side of the package into and including the recesses on the optically transmissive lid. The method may include singulating through the light blocking material to form a plurality of encapsulated semiconductor packages. The recesses may be on a first edge and a second edge of each of the optically transmissive lids around an opening in the light blocking material.

(8) Implementations of methods of forming semiconductor packages may include one, all, or any of the following: The method may include forming the plurality of recesses on the second side of the optically transmissive lid through one of etching or laser ablation. The light blocking material may include a molding compound. The method may further include forming a plurality of through silicon vias (TSVs), a passivation layer, a redistribution layer, a solder mask, and coupling solder bumps to each of the semiconductor packages. An opening in the light blocking material on each of the plurality semiconductor packages may correspond with an active area in the semiconductor die. The method may further include coupling dam material to the optically transmissive lid. The foregoing and other aspects, features, and advantages will be apparent to those artisans of ordinary skill in the art from the DESCRIPTION and DRAWINGS, and from the CLAIMS.

Description

BRIEF DESCRIPTION OF THE DRAWINGS

- (1) Implementations will hereinafter be described in conjunction with the appended drawings, where like designations denote like elements, and:
- (2) FIG. 1 is a cross sectional view of an implementation of a semiconductor package;
 - (3) FIG. 2 is a top view of an implementation of a semiconductor package;
 - (4) FIG. 3 is a side view of an implementation of an optically transmissive lid;
 - (5) FIG. 4 is a side view of an implementation of an implementation of a semiconductor wafer coupled with an implementation of an optically transmissive lid;
 - (6) FIG. 5 is side view of a panel of an implementation of a semiconductor packages after various processing steps;
 - (7) FIG. 6 is a cross sectional view of a semiconductor package after singulation;
 - (8) FIG. 7 is a cross sectional view of an implementation of two semiconductor packages coupled with an implementation of a carrier wafer;
 - (9) FIG. 8 is a cross sectional view of an implementation of two semiconductor packages after encapsulation with an implementation of a light blocking material;
 - (10) FIG. 9 is a cross sectional view of an implementation of a semiconductor package after

singulation; and

(11) FIG. 10 is a top view of an implementation of a top of a semiconductor package as described herein.

DESCRIPTION

(12) This disclosure, its aspects and implementations, are not limited to the specific components, assembly procedures or method elements disclosed herein. Many additional components, assembly procedures and/or method elements known in the art consistent with the intended semiconductor packages will become apparent for use with particular implementations from this disclosure. Accordingly, for example, although particular implementations are disclosed, such implementations and implementing components may comprise any shape, size, style, type, model, version, measurement, concentration, material, quantity, method element, step, and/or the like as is known in the art for such semiconductor packages, and implementing components and methods, consistent with the intended operation and methods.

(13) In various image sensor implementations, a transparent or translucent material is employed to cover the area of the image sensor die that is exposed to light. The transparent or translucent material of the cover or lid can allow light to enter package outside the sensor area which can result in flare being observed in the output from the image sensor. Referring to FIG. 1, an implementation of a semiconductor package 2 is illustrated. The semiconductor package includes a semiconductor die 4 coupled with an optically transmissive lid 6. The second side of the semiconductor die 4 is coupled to the first side of the optically transmissive lid 6. In various implementations, the optically transmissive lid 6 may include, by non-limiting example, glass, polycarbonate, acrylic, plastics, or other materials that allow some or all of a desired wavelength of light to pass through the material. In various implementations, the optically transmissive lid may be coupled to the semiconductor die through an adhesive material. In various implementations, the adhesive may include, by non-limiting example, epoxy, resin, polymers, glue, solders, and other adhesive materials used in coupling components of semiconductor devices. In some implementations, the adhesive may include silver or other metal fillers to create electrical conductivity for the adhesive. In some implementations, a dam 8 is coupled between the optically transmissive lid 6 and the semiconductor die 4. The dam may create a gap between the lid and the active area of the semiconductor die. In various implementations, the dam material may include, by non-limiting example, liquid epoxy, silicone, or other encapsulants that provide device protection, reduce warpage, demonstrate excellent flow, offer good adhesion to multiple substrates and have the strength to handle over-molding and subsequent process steps.

(14) Still referring to FIG. 1, the semiconductor package 2 also includes two through silicon vias (TSVs) 10 extending from a first side of the semiconductor die to a die pad 11 on the second side of the semiconductor die 4. Coupled to the first side of the semiconductor die 4 is a redistribution layer (RDL) 12 extending from a first edge of the semiconductor die 4 to a second edge of the semiconductor die 4. A ball grid array 14 is coupled to the first side of the semiconductor die 4 and is surrounded by the RDL 12.

(15) As illustrated, a light blocking material/masking material 16 surrounds the semiconductor package 2 extending from the first side of the semiconductor die 4 to a second side of the optically transmissive lid 6. The light blocking material 16 does not fully encapsulate the semiconductor package. As illustrated in FIG. 2, an opening 18 in the light blocking material 16 exists on the second side of the optically transmissive lid 6 that substantially corresponds with the active area of the semiconductor die (image sensor array). In various implementations, the light blocking material may be a molding compound. In other implementations, the light blocking material may include other materials that are capable of blocking light at any desired frequency from entering through the sides of the optically transmissive lid such as epoxies, resins, or polymers.

(16) The light blocking material may be capable of ensuring no light enters the package from non-sensor areas of the semiconductor package. Blocking light from entering non-sensor areas may

prevent flare. Flare may degrade the performance of the image sensor. Flare occurs when light bounces off metal pieces/structures in the semiconductor packages and into the sensor of the image sensor die. For example, metal structures may be exposed in the die streets of a semiconductor die after singulation. Without light blocking material around the sides of an optically transmissive lid, light may enter the lid from many angles and may reflect off the metal in the die streets. The stray light may enter directly on a side of the lid, hit the metal structures, reflect around within the lid and then hit the sensor of the die. Applying light blocking material around the edges of the optically transmissive lid results in a structure where light may only enter the portion of the optically transmissive lid that corresponds with the sensor or pixels of the semiconductor package thereby preventing light from reaching any metal structures within the semiconductor package. As a result of eliminating or substantially eliminating reflections from metal structures within the package, flare and the resulting image degradation caused by flare also prevented.

(17) As illustrated, the second side of the optically transmissive lid **6** has indentations **20** on each of a first edge **21** and a second edge **22** of the lid **6**. The light blocking material **16** may fill these indentations and the indentations **20** may prevent the light blocking material **16** from entering the opening **18**. Referring to FIG. 2, a top view of the opening **18** surrounded by the light blocking material **16** is illustrated. The opening **18** may correspond with a pixel array in the semiconductor die.

(18) Referring to FIG. 3, a cross sectional view of an optically transmissive lid **24** is illustrated. The optically transmissive lid **24** includes a plurality of recesses **26** formed on a first side of the lid. In some implementations, the plurality of recesses may be pre-formed in the optically transmissive lid. In other implementations, the plurality of recesses **26** may be formed through etching or laser ablation in combination with various patterning methods (such as photolithography). In various implementations, the etching may include wet etching or dry etching. Various implementations of methods of manufacturing semiconductor packages as described herein may be used including wafer level processes and panel level processes. Panel level processes may have cost and productivity advantages. Panel level processing may allow for parallel processing of more units of semiconductor packages in a given period compared with wafer level processes. Panel level processing may also reduce waste that results from processing partial die in a wafer level process. A method for forming a semiconductor package may include providing an optically transmissive lid as illustrated in FIG. 3. In various implementations, the optically transmissive lid may include, by non-limiting example, glass, polycarbonate, acrylic, plastics, or other materials that allow some or all of a desired wavelength of light to pass through the material.

(19) The method may further include coupling a semiconductor wafer to a first side of the optically transmissive lid. The semiconductor wafer may include a plurality of active areas on a second side of the wafer. In various implementations, the active areas may include pixel arrays. Referring to FIG. 4, a semiconductor wafer **28** coupled to an optically transmissive lid **24** is illustrated. The plurality of active areas **30** are enclosed in a gap **31** between the semiconductor material **28** and the optically transmissive lid **24**. Dams **34** on either side of each of the plurality of active areas **32** helps to form the gaps **31**. In various implementations, the dams **34** may be coupled to die pads **36** in the semiconductor wafer **28** on either side of the active areas **30**.

(20) Referring to FIG. 5, an implementation of a panel **37** of semiconductor packages is illustrated. In various implementations, the panel may be processed using a standard chip scale package process. For example, the method may include forming a plurality of through silicon vias (TSVs) **38** through the first side of the semiconductor wafer on either side of the active area **30**. The TSVs may be formed through drilling, etching, or other methods of forming a hole through a semiconductor die. The method may also include forming a passivation layer and RDL **40** over the plurality of semiconductor die **43**. The method may also include forming a solder mask and coupling a plurality of balls **42** to form a ball grid array (BGA) to the first side of the semiconductor die **43**. In various implementations, different surface mount interconnects such as,

by non-limiting example, pillars, stud bumps, and any other interconnect type may be used. In some implementations, the interconnects may be formed of copper, solder, or other electrically conductive materials.

(21) The method may also include singulating the semiconductor wafer and the optically transmissive lid between each of the plurality of active areas in the wafer to form a plurality of semiconductor packages. The packages may be singulated through sawing or dicing. Referring to FIG. 6, an implementation of a semiconductor package **44** after singulation is illustrated. The method also includes coupling each of the semiconductor packages to a carrier wafer. The second side of the optically transmissive lids **48** of each of the semiconductor packages **44** is coupled to the carrier wafer **49** as illustrated in FIG. 7. In various implementations, the semiconductor packages may be coupled to the carrier wafer through a pick and place process. Recesses are located on the first edge and the second edge of each of the optically transmissive lids. As illustrated, the recesses **26** on the second side of each of the optically transmissive lids **24** form a space **46** between the carrier wafer **49** and the optically transmissive lids **24**. The space is then filled with light blocking material allowing the light blocking material to encapsulate each of the packages and leave an opening on the second side of the optically transmissive lid. In various implementations, the opening is sized to expose only a sensor area of the semiconductor die. In other implementations, the opening may be sized to substantially expose only a sensor area of the semiconductor die.

(22) Referring to FIG. 8, the plurality of semiconductor packages **44** are illustrated after applying light blocking material **50** to each of the semiconductor packages. As previously described, the light blocking material **50** encapsulates each of the semiconductor packages from a first side of the packages into and including the recesses **26** on the optically transmissive lids **24**. In various implementations, the light blocking material **50** may include a molding compound. In various implementations, the molding compound may include, by non-limiting example, epoxies, resins, polymers, solders, and other materials that may be used to seal a die to a lid of a semiconductor package.

(23) The light blocking material may prevent stray light from entering the active area of the semiconductor die by preventing light from entering the semiconductor packages on the sides of the optically transmissive lid. In various implementations, the method also includes singulating through the light blocking material to form a plurality of encapsulated semiconductor packages. The semiconductor packages may be singulated through sawing or dicing.

(24) Referring to FIG. 9, an implementation of a semiconductor package **52** is illustrated. The package includes a semiconductor die **53** coupled to an optically transmissive lid **57**. The semiconductor die **53** includes a first side **54** and a second side **56**. The second side **56** of the semiconductor die **53** includes an active area including a pixel array. The second side **56** of the die **53** is coupled to the first side **59** of the optically transmissive lid **57**. In various implementations, the die and the lid may be coupled through adhesive material. By non-limiting example, the adhesive material may include epoxy, resin, polymers, glue, and other adhesive materials used in coupling components of semiconductor devices. In other implementations, the die and the lid may be coupled through dams. The dams may be formed of any of the materials previously mentioned herein. The dam creates a gap between the semiconductor die **53** and the optically transmissive lid **57**.

(25) A second side **58** of the optically transmissive lid **57** may include a first recess **60** and a second recess **62** on a first edge **64** and a second edge **66** of the optically transmissive lid **57**. The semiconductor package **52** also includes a light blocking material **68** encapsulating the semiconductor package from a first side of the semiconductor die into the first recess **60** and into the second recess **62** on the second side of the lid. Referring to FIG. 10, the opening **70** in the light blocking material **68** is sized to expose only, or substantially only, the sensor area of the semiconductor die. The size of the opening may prevent stray light from entering the sensor area in

the active area of the semiconductor die. In various implementations, the light blocking material may include a molding compound. As previously described, the light blocking material may include other materials that are capable of blocking visible light from entering through the sides of the optically transmissive lid in other implementations. The light blocking material may be capable of ensuring no light enters the package from non-sensor areas of the semiconductor package. Blocking light from entering non-sensor areas may prevent flare and enhance image quality.

(26) Referring again to FIG. 9, the semiconductor package also includes a redistribution layer (RDL) 72 coupled to the first side of the semiconductor die 53. The RDL 72 is coupled to die pads 74 through a plurality of through silicon vias (TSVs) 76. As illustrated, the die pads are located on either side of the active area of the image sensor die. The semiconductor package also includes a passivation layer, a solder mask, and two solder bumps 78 on the first side of the semiconductor die 53. In some implementations, more than two bumps may be coupled to a first side of the semiconductor die.

(27) Implementations of semiconductor packages described herein may have high reliability due to protection/molding being present on 6 sides of the semiconductor package. The light blocking material and related processes may be used in other implementations of image sensor packages such as, by non-limiting example, charge-coupled devices (CCD), complementary metal-oxide-semiconductor (CMOS) or N-type metal-oxide-semiconductor (NMOS, Live MOS) packages. It might be advantageous to apply light blocking material to any semiconductor package including an optically transmissive lid to prevent unwanted light from entering the package.

(28) In places where the description above refers to particular implementations of semiconductor packages and implementing components, sub-components, methods and sub-methods, it should be readily apparent that a number of modifications may be made without departing from the spirit thereof and that these implementations, implementing components, sub-components, methods and sub-methods may be applied to other semiconductor packages.

Claims

1. A method of forming an image sensor package, the method comprising: providing an optically transmissive lid comprising a first side and a second side, the optically transmissive lid comprising a plurality of recesses on the second side of the optically transmissive lid; coupling a semiconductor wafer to the first side of the optically transmissive lid; singulating the semiconductor wafer and the optically transmissive lid between each of a plurality of active areas in the semiconductor wafer to form a plurality of image sensor packages; coupling the second side of the optically transmissive lid of each image sensor package to a carrier wafer, wherein the plurality of recesses on the optically transmissive lid form a space between the carrier wafer and the optically transmissive lid; applying a light blocking material to each image sensor package, the light blocking material encapsulating each image sensor package from a first side of the package into and including the recesses on the optically transmissive lid; and singulating the plurality of image sensor packages into a plurality of encapsulated image sensor packages; wherein the light blocking material is configured to ensure that light only enters a portion of a single side of the optically transmissive lid of each image sensor package.
2. The method of claim 1, further comprising forming the plurality of recesses on the second side of the optically transmissive lid through one of etching or laser ablation.
3. The method of claim 1, wherein the light blocking material is configured to prevent flare.
4. The method of claim 1, further comprising forming a plurality of through silicon vias (TSVs), a passivation layer, a redistribution layer, a solder mask, and coupling solder bumps to each image sensor package.
5. The method of claim 1, wherein an opening in the light blocking material on each of the plurality image sensor packages corresponds with an active area in a semiconductor die.

6. The method of claim 1, wherein the image sensor package is a chip scale package.
 7. A method of forming an image sensor, the method comprising: providing an optically transmissive lid comprising a first side and a second side opposite the first side; coupling a semiconductor wafer to the first side of the optically transmissive lid; singulating the semiconductor wafer and the optically transmissive lid to form a plurality of image sensor packages; and applying light blocking material to each of the image sensor packages; wherein each of the image sensor packages are configured to receive light only through an opening through the light blocking material on the second side of the optically transmissive lid.
 8. The method of claim 7, wherein the image sensor package is a chip scale package.
 9. The method of claim 7, wherein the optically transmissive lid comprises a plurality of recesses in the second side.
 10. The method of claim 7, wherein the light blocking material comprises a mold compound.
 11. The method of claim 7, further comprising coupling the second side of the optically transmissive lids of each image sensor package to a carrier wafer prior to applying the light blocking material.
 12. The method of claim 7, wherein the light block material is configured to prevent flare within each image sensor package.
 13. The method of claim 7, wherein an outermost surface of the light blocking material covering the second side of the optically transmissive lid is coplanar with an outermost surface of the second side of the optically transmissive lid.
 14. A method of forming a semiconductor package, the method comprising: providing an optically transmissive lid comprising a first side and a second side opposite the first side, the optically transmissive lid comprising a plurality of recesses on the second side of the optically transmissive lid; forming a panel of semiconductor packages through coupling a semiconductor wafer to the first side of the optically transmissive lid; forming a plurality of through-silicon vias (TSVs) through the semiconductor wafer; coupling a redistribution layer over the semiconductor wafer; singulating the panel of semiconductor packages to form a plurality of semiconductor packages; coupling the second side of the optically transmissive lids of each semiconductor package to a carrier wafer; applying light blocking material to each semiconductor package, the light blocking material configured to prevent flare within each of the semiconductor packages; and singulating through the light blocking material to form a plurality of encapsulated semiconductor packages.
 15. The method of claim 14, further comprising forming the plurality of recesses on the second side of the optically transmissive lid through one of etching or laser ablation.
 16. The method of claim 14, wherein the light blocking material covers at least a portion of each side of each semiconductor package.
 17. The method of claim 14, wherein an opening in the light blocking material on each of the plurality semiconductor packages corresponds with an active area in a semiconductor die.
 18. The method of claim 14, further comprising forming a plurality of dams between the optically transmissive lid and the semiconductor wafer.
 19. The method of claim 14, wherein the semiconductor package is a chip scale package.
 20. The method of claim 14, wherein an outermost surface of the light blocking material covering the second side of the optically transmissive lid is coplanar with an outermost surface of the second side of the optically transmissive lid.
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